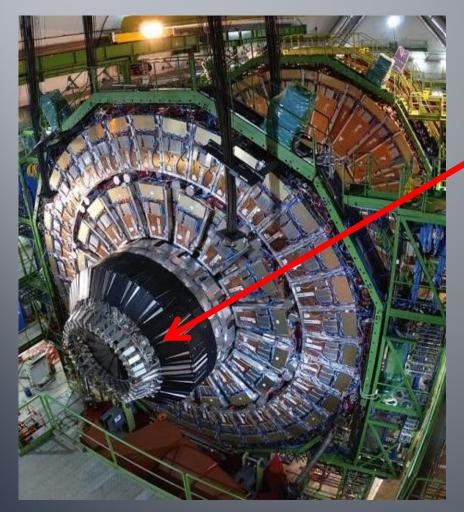
Summary

Large GEM

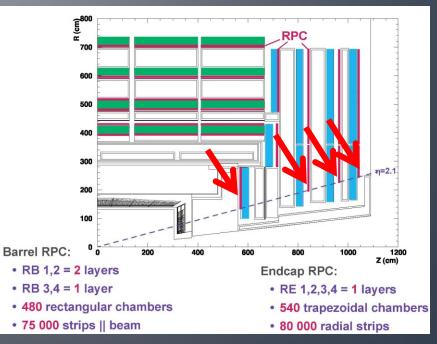
- CMS RE1-1
- Kloe
- Ns2 (No stretch No stress)
- Large Micromegas
 - Atlas MAMA project
- Large THGEM
 - Double phase pure argon project
- Equipment for large size detectors update
- Next workshop

CMS RE1-1 project

1m x 0.5m



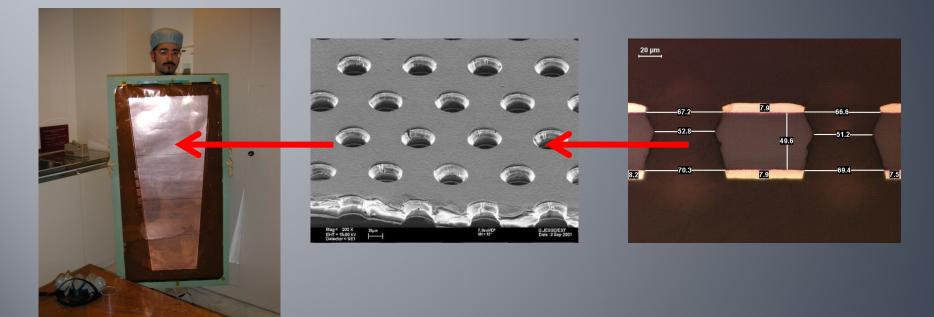
MPGD Vs RPC



14/12/2010

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-6 GEMs produced
-1m x 0.4m Single Mask
-Yield : 8 GEMs for 6 Good (process tuning)
-No problems due to GEMs in the final detector



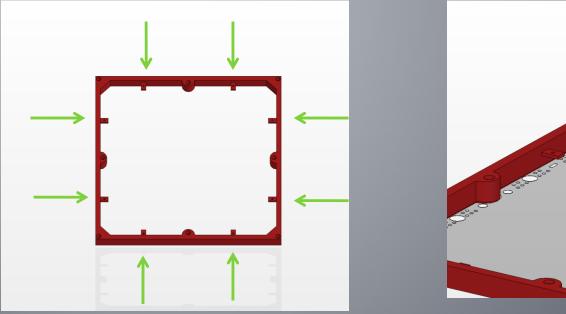


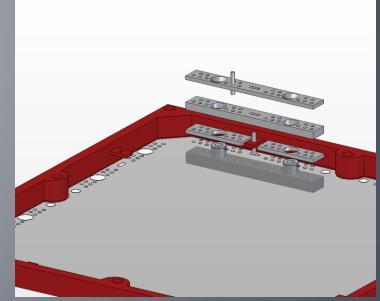
-Single mask process -1m x 400mm -Std hole pattern -Gem segmented (100cm2)

15 GEMs already produced and tested

New batch of 15 GEMs in production -delivery end of January

Ns2 project

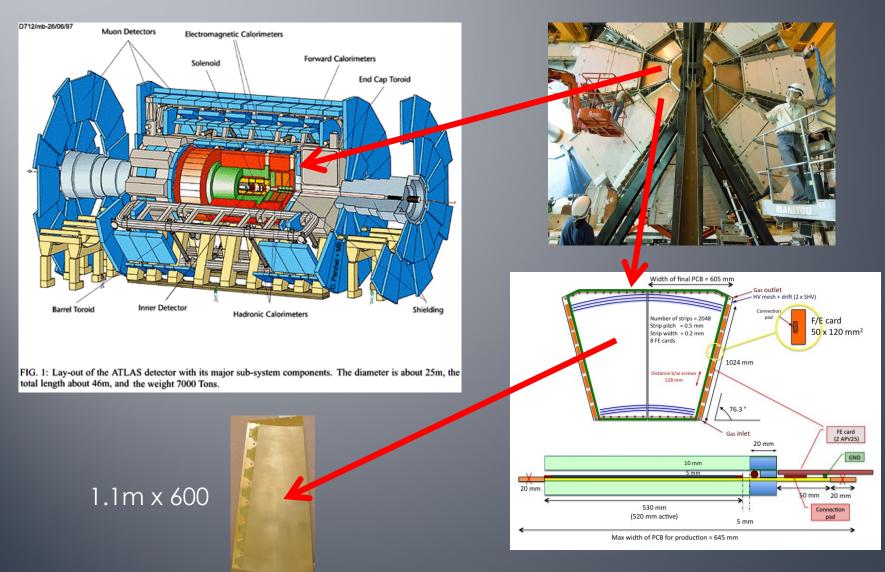




- -Triple GEM detector without spacers in active area -No tool for stretching
- -No gluing
- -Detachable
- -7 to 8mm Complex frame
- -Goal :1h assembly for a 100mm x 100mm detector

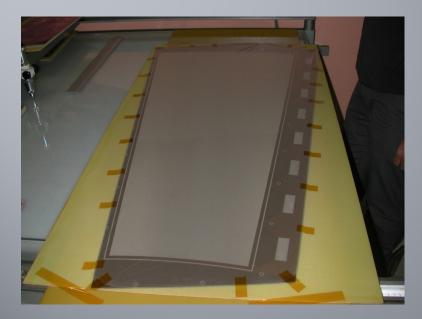
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Atlas MAMA project



14/12/2010

Atlas MAMA project



2 Bulks have been produced

- -1Standard Bulk (S1) -No production problems -Detector works
- -1Resistive Bulk (R1)
 -Leakage current → 2uA @ 500V?
 -Development problem?
 -One line connected to mesh?

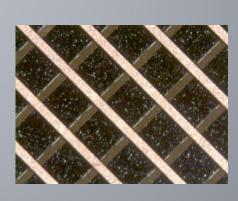


-Many cleaning procedure have been performed:

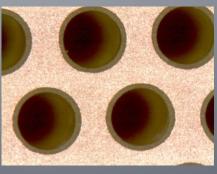
- -Potassium Permanganate
- -Concentrated Sulfuric acid
- -Karsher cleaning
- -Extremely robust structure

IHGEM and read-out for Double phase pure argon LEM-TPC with 2D anode









THGEM description: -800mm x 400mm Halogen Free -1mm & 2mm thick -RIM 40um (differential etching) -0.8mm pitch -0.5mm hole diameter

@ ELTOS:-Drilling-Photolithography-Differential etching

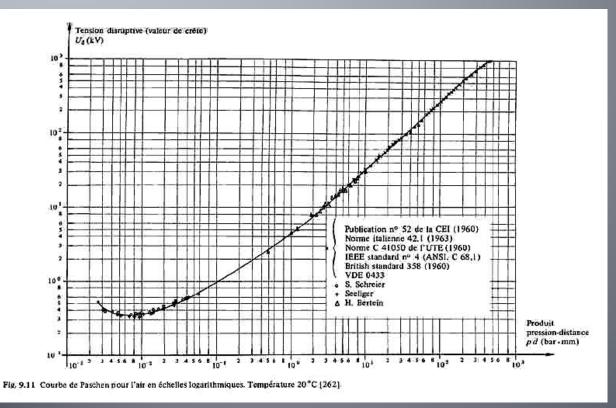
@ CERN:-Thermal treatment

- -Passivation
- -Cleaning
- -Electrical Test

@ CERN : full Read-out 2D production

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THGEM test



Tested in air

 $1 \text{mm} \rightarrow 4\text{KV}$ $2 \text{mm} \rightarrow 7\text{kV}$

Results are consistent with Paschen law in air

Equipment

Investment of 785 KChf 2010-2011

- Large developing machine (DR)
- Large copper etching machine (DR)
- Large stripping machine (DR)
- Large laminator (ordered)
- Large dryer (ordered)
- Large oven (OK)
- Large exposure machine(OK)
- Continuous Kapton etching machine(OK)
- Electro-chemical copper etching line(study)
- All the machine should be running by mid 2011

For the Next workshop

-Re Production of a large resistive BULK for MAMA

-Introduce the first 2 D Micromegas Read-out with only capacitive coupling and Resistive protection (R16)

-Ns2 project \rightarrow detector 100mm x 100mm